

Mask Laser Writer



- The Heidelberg DWL66 is located in the Class-100 clean room. This direct write system is used for single wafer exposures or making photolithography (chrome on glass) masters.
- The system is equipped with a 405nm diode laser for exposing patterns from a layout drawing, directly onto a photoresist coated surface
- Two exchangeable write heads allow writing resolutions of 2.5 μ m with the 10mm head and 0.8 μ m with the 2mm head.
- Handles substrate sizes up to 8" square.